INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)					Docket Number (Optional) 2002US303			Application Number 10/042,531			
					Applicant(s) Takan ri Kudo et al						
- JUL 1	JUL 1 1 2003 (Use several sheets if necessary)					m, 0, 2002		Group Art Unit 1752			
					January 9, 2002 1752 TENT DOCUMENTS						
*EXAMINER	IUE		U.S. FAT				SUBCLASS FILING DATE				
INITIAL	REF	DOCUMENT NUMBER	DATE		NAME		CLASS	SUBCLASS	IF APPRO		
								245			
						Ì		PECE WL 1 5 700 OUP 17	VED		
								WL 1 5 201	13		
				ļ	•	- ,	<u>G</u> F	W CAND	-		
				ļ				17	90		
					•						
				 							
			1-		·			 			
	:										
FOREIGN PATENT DOCUMENTS											
	REF	DOCUMENT NUMBER DATE			COUNTRY		CLASS	SUBCLASS	Trans YES	lation NO	
M	æ	WO 02 093263 A 1	11/21/2002	Europe							
										•	
								-			
									:		
	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)										
eA	Padmanaban et al, XP-008014024, "Materials and Resists for 193 and 157 nm Applications", Journal of Photopolymer Science and Technology, CHIBA, JP, vol. 14, no. 4, 2001, pages 631-642										
,,,			,, ,	, . ,	71 9						
	-					· · · · · · · · · · · · · · · · · · ·			· · · · · · · · ·	-	
			. <u></u> -								
EXAMINER R. Ashton.					DATE CONSIDERED						
		al if citation considered, whether clude copy of this form with next			ce with MPEP Secti	ion 609; Dra	aw line thro	ugh citation if not	in conform	ance and	

Form PTO-A820 (also form PTO-1449) P09A/REV04

Patent and Trademark Office * U.S. DEPARTMENT OF COMMERCE